**PATENT** IN THE UNITED STATES PATENT AND TRADEMARK OFFICE In re the application of: ) Group: 2125 M. Saldana ) Examiner: Kasenge, C. Application No: 10/789,486 Docket No: LAM2P255D1 Filed: February 26, 2004 Date: April 19, 2005 For: METHODS WITH RESOLUTION ENHANCEMENT FEATURE FOR IMPROVING ACCURACY OF CONVERSION OF REQUIRED CHEMICAL MECHANICAL POLISHING PRESSURE TO FORCE TO BE APPLIED BY POLISHING HEAD TO WAFER **CERTIFICATE OF MAILING** I hereby certify that this correspondence is being deposited with the United States Postal

Service as First Class Mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22, 13 1450 on April 19, 200

## COMMENTS ON STATEMENT OF REASONS FOR ALLOWANCE

Commissioner for Patents Alexandria, VA 22313-1450

Sir:

This is a response to the Statement of Reasons For Allowance mailed 2/7/05. Reference is made to the sentence in the Statement that includes "The allowability, at least in part, resides in the fact that neither reference teaches an apparatus...". Applicant notes that the allowed claims define various methods. Thus, it is respectfully requested that this sentence be revised to read as follows:

"The allowability, at least in part, resides in the fact that neither reference teaches a method comprising the operations of dividing the pressure range by the value of a component resolution to define scale portions of the pressure range, generating a first output signal to identify one of the scale portions that includes the desired value, and generating a second output signal to identify a set point that defines the requested value in the identified scale portion."

Respectfully submitted,

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